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**HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS**

Appl. No. : 09/991,196 Confirmation No. 3908  
Applicant : Chih-Chien Liu et al.  
Filed : November 20, 2001  
TC/A.U. : ~ 1796  
Examiner : SERGEANT, RABON A  
Docket No. : NAUP1068USA3  
Customer No. : 27765

Commissioner for Patents  
P.O. Box 1450  
Alexandria VA 22313-1450

**AMENDMENT**

Sir:

- 5 In response to the NOTICE OF ALLOWANCE AND FEE(S) DUE on December 21, 2009. According to **37 CFR 1.312**, applicant would like to amend some typos, which merely embody the correction of formal matters without changing the scope of the claims. Please amend the above -identified applications as follow:

- 10 **Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 8 of this paper.